

CONFERENCE AT A GLANCE

Date	Time	TUTORIALS				
Monday 3/21/05	9:00am-5:00pm	Design of sub-90nm CMOS Circuits and Design Methodologies Package-Chip Co-Design – Strategies & Challenges Room: San Carlos/San Juan				
	6:30pm-8:30pm	Evening Panel Discussion EP1 IP Creation and Use What roadblocks are ahead or it is just clear and bumpy road?				
Tuesday 3/22/05	8:30am-10:15am	PLENARY SESSION 1P Keynote Speeches by: John Kibarian, Ashok K. Sinha, Joe Sawicki				
	10:15am-10:30am	Morning Break				
	10:30am-12:00pm	Session 1A Tools and Flows for Quality Design Room: San Carlos	Session 1B High Level Power/Noise Reduction Techniques Room: San Juan	Session 1C Leakage and Dynamic Power Issues Room: San Martin	Session 1D Poster City Foyer	
	12:00pm-1:00pm	ISQED LUNCHEON (Sponsored by Synopsys) Committee Recognition Awards Best Paper Awards (Sponsored by Synopsys)				
		IP Quality: A Design, not a Verification Problem Michael Keating				
	1:00pm-3:05pm	Session 2A Test Application and Cost Reduction Room: San Carlos	Session 2B DFM and Physical Layout Room: San Juan	Session 2C Performance and Reliability Analysis for Yield Optimization Room: San Martin		
	3:05pm-3:15pm	Afternoon Break				
	3:15pm-5:15pm	Session 3A Functional Verification and Test Generation Room: San Carlos	Session 3B Power Delivery and Distribution Room: San Juan	Session 3C Quality System Level Design and Synthesis Room: San Martin		
	5:15pm-6:50pm	Session 4A DFM for Circuit Design Room: San Carlos	Session 4B Leakage and Reliability Management Room: San Juan	Session 4C Analog Test and BIST Room: San Martin		
	7:00pm-9:00pm	Evening Panel Discussion EP2 Nanoelectronics: Evolution or Revolution?				
Wednesday 3/23/05	8:30am-10:15am	PLENARY SESSION 2P Keynote Speeches by: Jim Miller, Kurt A. Wolf, Bernard Candaele				
	10:15am-10:30am	Morning Break				
	10:30am-12:00pm	SESSION 5A Design Methods and Tools in DSM Room: San Carlos	SESSION 5B Design Techniques for Leakage Reduction Room: San Juan	SESSION 5C Variability Issues in Nanoscale Circuits Room: San Martin		
	12:00pm-1:00pm	LUNCH BREAK				
	1:00pm-3:05pm	SESSION 6A Issues in Noise and Timing Room: San Carlos	SESSION 6B Design Approaches for System in Package (SiP) Room: San Juan	SESSION 6C DSM Interconnect Issues Room: San Martin		
	3:05pm-3:30pm	Afternoon Break				
	3:30pm-5:35pm	SESSION 7A Advances in Floor Planning Room: San Carlos	SESSION 7B Issues in On-Chip Communication and Analog/RF Designs Room: San Juan	SESSION 7C Robust Design under Parameter Variations Room: San Martin		

TUTORIALS

San Carlos/San Juan

TUTORIAL I
9:00am-12:00pm

Design of sub-90nm Circuits and Design Methodologies

Chair & Moderator:
Anirudh Devgan, IBM Research

Speakers:
Ruchir Puri, Research Staff Member, IBM TJ Watson Research Center, NY
Sachin Sapatnaker, Professor, Electrical & Computer Engineering, University of Minnesota
Tanay Karnik, Principal Engineer, Intel Circuit Research Labs, Hillsboro, OR
Rajiv Joshi, Research Staff Member, IBM T J Watson Research Center, NY

SUMMARY:

This tutorial discusses design challenges of scaled CMOS circuits in sub-90nm technologies and the design methodologies required to design them in order to produce robust designs with desired power performance trade-off. We will focus on four major components: Design challenges of sub-90nm CMOS circuits with particular emphasis on implications of each individual device scaling element on circuit design: To continue scaling of the CMOS devices deep into sub-90nm technologies, fully depleted SOI, strained-Si on SiGe, FinFETs with double gate, and even further, three-dimensional circuits will be utilized to design high-performance circuits. We will discuss unique design aspects and issues resulting from this scaling such as gate-to-body tunneling, self-heating, reliability issues, and process variations. As the scaling approaches various physical limits, new design issues such as V_t modulation due to leakage, low-voltage impact ionization, and higher $V_{t_{in}}$ to maintain adequate $V_{t_{sat}}$, continue to surface. In this part of tutorial, we will discuss these emerging trends and design issues related to aggressive device scaling.

Design methodologies for implementing robust circuits with desired power performance characteristics: With device dimensions approaching their physical limits, design methodologies are playing increasing significant role in achieving desired power and performance. In deep-submicron designs, chip performance is increasingly limited by the interconnect delay. Transistor delays decrease with technology scaling, while the narrower metal lines and space increase the relative delay associated with the interconnects. As the designs are scaled to the next technology generation, the capacity of a same-sized die doubles, and the complexity and gate count of the design grows. This results in devices and interconnects wires being placed in ever-increasing proximity. As a result, the cross-coupling capacitance between adjacent wires is increasing with each technology generation. All of these trends indicate that interconnect delays in sub-90nm technologies will continue to dominate the overall chip performance. The dominant interconnect delays require accurate net length and delay prediction during timing optimization to improve circuit performance. Not only does the design of circuits in sub-90nm technologies require a high-performance logic synthesis system but it also necessitates seamless integration of placement and synthesis design environments. In addition, with the coupling-capacitance issues generating increasing difficulties for design closure, more accurate wire routes must be known while optimizing the design in order to fix these problems earlier in the design cycle. This requires close integration of interconnect routing environment with placement and synthesis environments. In this part of tutorial, we will present the details of a high-performance synthesis system and a design flow in which placement, synthesis, and routing environments closely and seamlessly interact with each other to handle flat designs that are over 5 million gates with fast turn around design times in 90nm CMOS technology.

Managing leakage power: It is well known that with CMOS technologies beyond 90nm, leakage power is one of the most crucial design components which must be efficiently controlled in order to utilize the performance advantage from these technologies. We will focus on various techniques to analyze and control all components of leakage power placing particular emphasis on sub-threshold and gate leakage power. In addition, this part of tutorial will discuss low voltage circuit design under high intrinsic leakage, leakage monitoring and control techniques, effective transistor stacking, multi-threshold CMOS, dynamic threshold CMOS, well biasing techniques, and design of low leakage data-paths and caches.

Circuit Design in the Presence of Uncertainty: Nanometer design technologies must work under tight operating margins, and are therefore highly susceptible to any process and environmental variabilities. This part of the tutorial will consider several factors related to reliability and yield. With regard to environmental variations, it is important to build circuits that have well-distributed thermal properties, and to carefully design supply networks to provide reliable V_{dd} and ground levels throughout the chip. On the process variation front, the effects of uncertainties in process variables must be modeled using statistical techniques, and they must be utilized to determine variations in the performance parameters of a circuit. Instead of pessimistically treating timing in a worst-case manner as is conventionally done in static timing analysis, statistical techniques will have to be employed that directly predict the percentage of circuits that are likely to meet a timing specification.

TUTORIAL II

1:00pm-5:00pm

Modeling and Design of Chip-Package Interface

Chair & Moderator:

Anirudh Devgan, IBM Research

Speakers:

Luca Daniel, Massachusetts Institute of Technology, Cambridge, MA

Byron Krauter, IBM Microelectronics, Austin, TX

Lei He, UCLA EE Dept, Los Angeles, CA

SUMMARY:

Signal integrity (SI) and power integrity are forecasted to be paramount issues for future chip and package designs. Larger number of IOs, higher frequencies, and tighter noise margins necessitate the merging of the design paradigms for chip IO and package. In this tutorial, we will shed light on a new chip-package co-design paradigm and all the technologies necessary to enable it. We will first discuss parameterized reduced order models accounting for all high frequency SI effects in the package that can be reliably and automatically extracted by field solvers. We will then introduce package-aware chip IO planning and placement, which is the key to chip-packaging co-design. Finally, we will cover detailed power and signal integrity modeling and optimization in package.

Session EP1

Panel Discussion & Dinner

Donner Pass Room

6:30pm - 8:30pm

IP Creation and Use

What roadblocks are ahead or it is just clear and bumpy road?

Panel Organizer: Pallab Chatterjee, SiliconMap

Panel Moderator: Stephen Ohr, EETimes

As custom (Analog & MS device level) design progresses into smaller process geometries, companies are faced with many challenges with new names - DFM, DFY, DIR, OPC/RET/MDP, DR and new tools in the EDA/CAD space. A great many of the issues have been around since the start of the IC industry; they are just getting new attention. This panel of seasoned veterans and technology innovators will discuss the change in the scope of the work effort involved in custom design in the 180-47nm process technologies and if the design superhighway has turned into a dead end with insurmountable roadblocks or simply a very bumpy side road in need of significant repair and upgrade.

Panelists:

Joachim Kunkel, Vice President of Engineering, DesignWare, Synopsys

Naveed Sherwani, Co-Founder, President & CEO of Open-Silicon

Kevin MacLean, Vice President, PDF Solutions

Jeff Lewis, Ciranova

Mark Rubin, Intersil Corp

Ken Brock, Silvaco Data Systems

Plenary Session 1P**Donner Pass Room****8:30AM - 10:15AM**

Co-Chairs: **Kris Verma**
Silicon Valley Technical Institute
Kenneth Shepard
Columbia University

8:30am**Introduction & Announcements****8:45am****1P.1 Enabling True Design for Manufacturability****John Kibarian**

President & CEO, PDF Solutions

Without any doubt, Design For Manufacturability has been the hottest buzzword for the last couple of years. This is quite justifiable by the enormous challenges in nanometer technology nodes and ever increasing design-process interactions. As a result, virtually all EDA companies have focused on providing the "DFM Solutions". Since the concept of DFM covers an extremely broad spectrum of tasks from the system level all the way to the manufacturing process, many of these DFM solutions are just the re-labeled design verification tasks.

In this talk, we will provide a more thorough classification of various DFM activities with the emphasis on the design tasks. We will also discuss the necessary condition to enable true DFM, i.e., the comprehensive characterization of the design-process interactions. We will present a complete process characterization methodology that is capable of extracting all the salient process variations for a full set of product design attributes. We will illustrate our talk by showing the yield loss Pareto for the leading technology nodes that will cover all the dominant yield loss phenomena including random, systematic and parametric mechanisms. We will also demonstrate example of design flows that take advantage of such a comprehensive characterization together with silicon results demonstrating the advantages of true DFM.

9:15am**1P.2 Recent progress and remaining challenges in pattern transfer technologies for advanced chip designs****Ashok K. Sinha**

Sr. VP & GM

Applied Materials, Inc

Even as the Moore's law continues to drive "tiny technologies" through relentless scaling, the main technology driver for semiconductor chips has evolved from DRAMs to Microprocessors to FPGAs. The underlying metrics have evolved from bits per chip and cost per bit for computers to functions per chip and cost per function for consumer products. This talk will review the remarkable progress that has been made in enabling pattern transfer technologies, including mask design, lithography enhancements and precision etching on the new 300mm wafers for an increasingly wide variety of new materials. However, there is a cost associated with all this and the cost-benefit tradeoffs will almost certainly drive new inflections in the entire food chain, which I will try to identify.

9:45am**1P.3 Shifting Perspectives on DFM****Joe Sawicki**

Vice President & General Manager

Mentor Graphics

In micron technologies, manufacturing constraints were captured in process technology rule files. This process information was accessed at different levels of abstraction during various stages in the design flow. In addition, design teams implemented best practice methodologies and 'experience-based' guidelines throughout the design chain to ensure acceptable yield and adequate test coverage.

So what changed in the quest for an optimum DFM methodology? Nanometer technology has ushered in new and significant yield and manufacturing considerations and constraints. The lack of major increase in yield improvement between the 350nm and 180nm nodes suggests that the yield loss mechanisms are not only increasing in numbers, magnitude, and complexity at each successive generation, but they are increasing at a rate fast enough to largely offset 'cosmetic' improvements in tools and methodologies.

If EDA tools are to assist the semiconductor industry at the 90nm and 65nm nodes, there must be profound changes to existing tools, and the introduction of new technologies that allow designers to consider and optimize for manufacturing at each stage of the design, verification, tapeout and test process.

Where will these new tools and capabilities appear? They will show up in all parts of the design flow, as well as on the manufacturing floor. In particular, an immediate focus for the EDA industry must center on delivering new technology in four key areas: process modeling (electrical and lithographic), statistical analysis and visualization, design optimization and Test and inspection.

Session 1A
San Carlos Room
10:30AM - 12:05PM

Tools and Flows for Quality Design

Chairs: Tom Chen, Colorado State University
Syed M. Alam, Freescale Semiconductor

10:30am

Introduction

10:35am

1A.1

Toward High Quality Tools and Tool Flows Through High-Performance Computing

Aaron N.L. Ng, Igor L. Markov, University of Michigan

11:05am

1A.2

Noise Library Characterization for Large Capacity Static Noise Analysis Tools

Alex Gyure, Alireza Kasnavi, Sam Lo, Peivand F. Tehrani, William Shu, Mahmoud Shahram, Joddy W. Wang, Jindrich Zedja, Synopsys Inc.

11:35am

1A.3

Two-Dimensional Layout Migration by Soft Constraint Satisfaction

Qianying Tang, Jianwen Zhu, University of Toronto

11:50am

1A.4

Domain Strategy and Coverage Metric for Validation

Luo Chun, Yang Jun, Shi Longxing, Wu XuFan, Zhang Yu, Southeast University, China

Session 1B
San Juan Room
10:30AM - 12:05PM

High Level Power/Noise Reduction Techniques

Chairs: Farzan Fallah, Fujitsu Laboratories of America
Norman Chang, Apache Design Solutions

10:30 am

Introduction

10:35am

1B.1

Power Supply Noise-Aware Scheduling and Allocation for DSP Synthesis

Dongku Kang, Yiran Chen, Kaushik Roy, Purdue University

11:05am

1B.2

Reducing Power Consumption during TLB Lookups in a PowerPC Embedded Processor

Shivakumar Swaminathan, Sanjay B. Patel, James Dieffenderfer, Joel Silberman, IBM

11:35am

1B.3

TFT-LCD Application Specific Low-Power SRAM Using Charge-Recycling Technique

Kee-Jong Kim, Chris H. Kim, Kaushik Roy, Purdue University

11:50am

1B.4

Error Analysis for the Support of Robust Voltage Scaling

David Roberts, Todd Austin*, David Blaauw*, Krisztian Flautner**, Trevor Mudge*, *University of Michigan, **ARM Ltd., UK*

Session 1C

San Martin Room

10:30AM - 12:05PM

Leakage and Dynamic Power Issues

Chairs: Paul Tong, Pericom Semiconductor
Naehyuck Chang, Seoul National University

10:30am

Introduction

10:35am

1C.1

Analytical Study of Impact Ionization and Subthreshold Current in Submicron N-MOSFET

Bhavana Jharia, S. Sarkar R. P. Agarwal, Dept. of E& CE, Indian Institute of Technology, Roorkee-INDIA

11:05am

1C.2

Analysis and Optimization of Static Power Considering Transition Dependency of Leakage Current in VLSI Circuits

Afshin Abdollahi, Farzan Fallah**, Massoud Pedram*, *University of Southern California, **Fujitsu Laboratories of America, Inc.*

11:35am

1C.3

Controlled-Load Limited Switch Dynamic Logic Circuit

Jayakumaran Sivagnaname, Hung C. Ngo, Kevin J. Nowka, Robert K. Montoye, Richard B. Brown, University of Michigan

11:50am

1C.4

Dynamically Pulsed MTCMOS with Bus Encoding for Total Power and Crosstalk Minimization

Harmander S. Deogun, Rahul M. Rao, Dennis Sylvester, Richard Brown, Kevin Nowka, University of Michigan

Session 1D

City Foyer

10:30AM - 3:15PM

Poster Session

Chairs: James Lei, Altera
Israel Koren, University of Massachusetts Amherst

1D.1

Non-Charge-Sheet Core and Architecture of BSIM5

Jin He, Jane Xi, Mansun Chan, Hui Wan, Mohan Dunga, Babak Heydari., Ali M. Niknejad, Chenming Hu, University of California, Berkeley

1D.2

Integration of DFM Practices in Design Flows

L.Riviere Cazaux, Freescale Semiconductors

1D.3

How Circuit Analysis and Yield Optimization Can Be Used to Detect Circuit Limitations before Silicon Results

Carlo Roma, Pierluigi Daglio, Guido De Sandre, Marco Pasotti, Marco Poles, STMicroelectronics

1D.4

Leakage Current Modeling in Pd SOI Circuits

Mini Nana, David Blaauw**, MI, Chanhee Oh***, *Sun Microsystems, Austin, TX, **University of Michigan, ***Nascentric, Austin, TX*

1D.5

A Balanced Scorecard for Systemic Quality in Electronic Design Automation: An Implementation Method for an EDA Company

Jasjeet Kaur, Mentor Graphics

1D.6

RCL Characterization and Modeling of X Architecture Diagonal Wires for VLSI Design

Narain D. Arora, Li Song, Santosh Shah, Kalyan Thumaty, Aki Fujimura, Victor Chang, S. Y. Cho*, Cadence Design Systems, *TSMC*

1D.7

A Technique for Designing Totally Self-Checking Domino Logic Circuits

C.K. Tang, P.K. Lala, J.P. Parkerson, University of Arkansas

1D.8

Early Assessment of Leakage Power For System Level Design

C. Talarico, B.S. Pillilli, K.L. Vakata, J.M. Wang, University of Arizona

1D.9

Technology Mapping For Reliability Enhancement in Logic Synthesis

Zhaojun Wo, Israel Koren, University of Massachusetts Amherst

1D.10

Evaluation of Capacitor Ratios in Automated Accurate Common-Centroid Capacitor Arrays

Diaaeldin Khalil, Mohamed Dessouky*, Vincent Bourguet**, Marie-Minerve Louërat**, Andreia Cathelin***, *Hani Ragai Ain Shams University, Egypt, **University of Paris 6, France, ***STMicroelectronics, France*

1D.11

Closing the Gap Between Carry Select Adder and Ripple Carry Adder: A New Class of Low-Power High-Performance Adders

Behnam Amelifard, Farzan Fallah**, Massoud Pedram*, *University of Southern California, **Fujitsu Laboratories of America, Inc.*

1D.12

Capacitance and Yield Evaluations Using a 90-Nm Process Technology Based on the Dense Power-Ground Interconnect Architecture

Atsushi Kurokawa, Masaharu Yamamoto, Nobuto Ono, Tetsuro Kage, Yasuaki Inoue, Hiroo Masuda, Semiconductor Technology Academic Research Center, Japan

1D.13

Testing for Resistive Shorts in FPGA Interconnects

Haixia Gao, Yintang Yang, Xiaohua Ma, Gang Dong, Xidian University, P.R. China

1D.14

TED Thermo-Electrical Designer: A New Physical Design Verification Tool

Sokolowska Ewa, Barszcz Marek, Kaminska Bozena, Pultronics Inc.

1D.15

A Fast Lithography Verification Framework for Litho-Friendly Layout Design

Yong-Chan Ban, Soo-Han Choi, Ki-Hung Lee, Dong-Hyun Kim, Ji-Suk Hong, Yoo-Hyon Kim, Moon-Hyun Yoo, Jeong-Taek Kong, Samsung, South Korea

1D.16

Gate-Level Mitigation Techniques for Neutron-Induced Soft Error Rate

Harmander S. Deogun, Dennis Sylvester, David Blaauw, University of Michigan

1D.17

Exact Algorithms for Coupling Capacitance Minimization by Adding One Metal Layer

Hua Xiang, Kai-Yuan Chao, Martin D.F. Wong, IBM

1D.18

Design of a 10-bit TSMC 0.25um CMOS Digital to Analog Converter

J. Huynh, B. Ngo, M. Pham, Lili He, San Jose State University

1D.19

A High-Performance SRAM Technology with Reduced Chip-Level Routing Congestion for SOC
R. Castagnetti, R. Venkatraman, B. Bartz, C. Monzel, T. Briscoe, A. Teene, S. Ramesh, LSI Logic

1D.20

Design and Evaluation of a Security Scheme for Sensor Networks
Khadija Stewart, Themistoklis Haniotakis, Spyros Tragoudas, Southern Illinois University Carbondale

1D.21

A Minimum Cut Based Re-Synthesis Approach
M. Welling, S. Tragoudas, H. Wang, Southern Illinois University Carbondale

1D.22

Analysis for Complex Power Distribution Networks Considering Densely Populated Vias
Young-Seok Hong, Heeseok Lee, Joon-Ho Choi, Moon-Hyun Yoo, Jeong-Taek Kong, Samsung Korea

1D.23

Buffer Planning Algorithm Based on Partial Clustered Floorplanning
Yuchun Ma, Xianlong Hong, Sheqin Dong, Song Chen, Chung-Kuan Cheng, Tsinghua University, China

1D.24

Issues and Challenges in Ramp to Production
Ravi Arora, Arun Shrimali, Anand Venkitachalam, Texas Instruments

ISQED Luncheon Awards & Speech **Donner Pass Room** *12:00pm-1:00pm*

Chairs: Ali Iranmanesh, Silicon Valley Technical Institute
Kaustav Banerjee, University of California at Santa Barbara

12:05pm

Committee Recognition Awards
Best Paper Awards (Sponsored By Synopsys)

12:25pm

Luncheon Speech:

IP Quality: A Design, not a Verification Problem

Michael Keating
Synopsys Inc.

Session 2A **San Carlos Room** *1:00PM - 3:05PM*

Test Application and Cost Reduction

Chairs: Sreejit Chakravarty, Intel
David Bonyuet, Delta Search Labs

1:00pm

Introduction

1:05pm

2A.1 Reseeding-Based Test Set Embedding With Reduced Test Sequences
E. Kalligeros, D. Kaseridis, X. Kavousianos, D. Nikolos, University of Patras, Greece

1:35pm

2A.2 Reduced Test Application Time Based On Reachability Analysis
Th. Haniotakis, S. Tragoudas, G. Pani, ECE Dept., Southern Illinois University

2:05pm

2A.3 Using MUXs Network to Hide Bunches of Scan Chains

*Yinhe Han**, *Yu Hu***, *Huawei Li***, *Xiaowei Li**, **Institute of Computing Technology, Chinese Academy of Sciences, Beijing,*
***Graduate School of Chinese Academy of Sciences, Beijing*

2:35pm

2A.4 BIST-Guided ATPG

Ahmad A. Al-Yamani, Edward J. McCluskey, Stanford University

3:05pm

2A.5 Dynamic Test Compaction for Bridging Faults

Irith Pomeranz and Sudhakar M. Reddy, Purdue University

Session 2B

San Juan Room

1:00PM - 3:05PM

DFM and Physical Layout

Chairs: *Enrico Malavasi, PDF Solutions*
Kris Verma, Silicon Valley Technical Institute

1:00pm

Introduction

1:05pm

2B.1

A Min-Variance Iterative Method for Fast Smart Dummy Feature Density Assignment in Chemical-Mechanical Polishing

Xin Wang, Charles Chiang, Jamil Kawa, Qing Su, Synopsys Inc.

1:35pm

2B.2

Standard Cell Printability Grading and Hot Spot Detection

Michel Cote Philippe Hurat, Synopsys Inc.

2:05pm

2B.3

Performance Driven OPC for Mask Cost Reduction

*Puneet Gupta**, *Andrew B. Kahng**, *Dennis Sylvester***, *Jie Yang***, **University of California at San Diego, **University of Michigan*

2:35pm

2B.4

Meeting Nanometer DPM Requirements through DFT

Jay Jahangiri, David Abercrombie, Mentor Graphics

Session 2C

San Martin Room

1:00PM - 3:05PM

Performance and Reliability Analysis for Yield Optimization

Chairs: *Amir Ajami, Magma Design Automation*
Adrian Ionescu, Swiss Federal Institute of Technology (EPFL)

1:00pm

Introduction

1:05pm

2C.1

Parametric Yield Analysis and Constrained-Based Supply Voltage Optimization

Rahul Rao, Kanak Agarwal, Anirudh Devgan, Dennis Sylvester, Richard Brown, Kevin Nowka, University of Michigan

1:35pm

2C.2

Power-Delay Metrics Revisited for 90nm CMOS Technology

Dipanjana Sengupta, Resve Saleh, University of British Columbia, Canada

2:05pm

2C.3

Optimization of Individual Well Adaptive Body Biasing (IWABB) Using a Multiple Objective Evolutionary Algorithm

Justin Gregg, and Tom W. Chen, Colorado State University

2:35pm

2C.4

Electromigration Reliability Comparison of Cu and Al Interconnects

Syed M. Alam, Frank L. Wei, Chee L. Gan**, Carl V. Thompson, Donald E. Troxel, *Freescale Semiconductor, **Nanyang Technological University, Massachusetts Institute of Technology*

Session 3A
San Carlos Room
3:15PM - 5:15PM

Functional Verification and Test Generation

Chairs: Daniela De Venuto, Politecnico di Bari, Italy

George Alexiou, University of Patras and Computer Technology Institute, Greece

3:15pm

Introduction

3:20pm

3A.1

Combining System Level Modeling with Assertion Based Verification

Anat Dahan, Daniel Geis*, Leonid Gluhovsky*, Dmitry Pidan*, Gil Shapir*, Yaron Wolfsthal*, Lyes Benalycherif**, Romain Kamdem**, Younes Lahbib**, *IBM Haifa Research Lab, Haifa Israel, **STMicroelectronics, Grenoble, France*

3:50pm

3A.2

Low Voltage Test In Place of Fast Clock in DDSI Delay Test

Haihua Yan, Gefu Xu, Adit D. Singh, Auburn University

4:20pm

3A.3

Functional Verification of Networked Embedded Systems

Nicola Bombieri, Franco Fummi, Graziano Pravadelli

4:50pm

3A.4

Functions for Quality Transition Fault Tests

Maria K. Michael, Stelios Neophytou*, Spyros Tragoudas**, *University of Cyprus, **Southern Illinois University, Carbondale*

Session 3B
San Juan Room
3:15PM - 5:15PM

Power Delivery and Distribution

Chairs: Ravi Joshi, IBM
David Overhauser, Cadence Design Systems

3:15pm

Introduction

3:20pm

3B.1

Noise Aware Decoupling Capacitors for Multi-Voltage Power Distribution Systems

Mikhail Popovich, Eby G. Friedman, University of Rochester

3:50pm

3B.2

P/G Pad Placement Optimization: Problem Formulation for Best IR Drop

Aishwarya Dubey, Texas Instruments

4:20pm

3B.3

Impact of On-Chip Inductance on Power Distribution Network Design for Nanometer Scale Integrated Circuits

Navin Srivastava, Xiaoning Qi, Kaustav Banerjee, University of California at Santa Barbara

4:50pm

3B.4

Power Grid Planning for Microprocessors and SOCs

Qing K. Zhu

Session 3C
San Martin Room
3:15PM - 5:15PM

Quality System Level Design and Synthesis

Chairs: Lech Jozwiak, Eindhoven University of Technology, The Netherlands
Artur Chojnacki, PDF Solutions

3:15pm

Introduction

3:20pm

3C.1

A Power-Aware GALS Architecture for Real-Time Algorithm-Specific Tasks

Animesh Datta, Swarup Bhunia, Nilanjan Banerjee, Kaushik Roy, Purdue University

3:50pm

3C.2

An ILP Formulation for Reliability-Oriented High-Level Synthesis

Suleyman Tosun, Ozcan Ozturk**, Nazanin Mansouri*, Ercument Arvas*, Mahmut Kandemir**, Yuan Xie**, *Syracuse University, **Pennsylvania State University*

4:20pm

3C.3

Analysis of the Effect Of LUT Size on FPGA Area and Delay Using Theoretical Derivations

Haixia Gao, Yintang Yang, Xiaohua Ma, Gang Dong, Xidian University, China

4:50pm

3C.4

Reliability-Centric Hardware/Software Co-Design

Suleyman Tosun, Nazanin Mansouri*, Ercument Arvas*, Mahmut Kandemir**, Yuan Xie**, *Syracuse University, **Pennsylvania State University*

Session 4A
San Carlos Room
5:15PM – 6:50PM

DFM for Circuit Design

Chairs: Sani Nassif, IBM
Nagib Hakim, Intel

5:15pm

Introduction

5:20pm

4A.1

Deep Submicron CMOS Integrated Circuit Reliability Simulation with SPICE

Xiaojun Li, B. Huang, J. Qin, X. Zhang, M. Talmor, Z. Gur, Joseph B. Bernstein, University of Maryland

5:50pm

4A.2

Modeling Layout Effects for Sensitivity-based Analog Circuit Optimization

Henry H. Y. Chan, Zeljko Zilic, McGill University

6:20pm

4A.3

In-Circuit Self-Tuning of Clock Latencies

Kambiz Rahimi, Chris Diorio**, *Impinj Inc., **University of Washington*

6:35pm

4A.4

Statistical Analysis of Clock Skew Variation in H-tree Structure

Masanori Hashimoto, Tomonori Yamamoto, Hidetoshi Onodera, Osaka University, Japan

Session 4B
San Juan Room
5:15PM – 6:50PM

Leakage and Reliability Management

Chairs: Panda Rajendran, Freescale Semiconductor
Seung H. Kang, Agere Systems

5:15pm

Introduction

5:20pm

4B.1

Modeling and Analysis of Gate Leakage In Ultra-Thin Oxide Sub-50nm Double Gate Devices And Circuits

Saibal Mukhopadhyay, Keunwoo Kim**, Jae-Joon Kim**, Shih-Hsien Lo**, Rajiv V. Joshi**, Ching-Te Chuang**, Kaushik Roy*, *Dept. Of ECE, Purdue University, **IBM T. J. Watson Research Center, Yorktown Heights*

5:50pm

4B.2

Design for Degradation: Cad Tools for Managing Transistor Degradation Mechanisms

G Ananth Somayaji, Gautam Kapila, Texas Instruments

6:20pm

4B.3

A Practical Transistor-Level Dual Threshold Voltage Assignment Methodology

Puneet Gupta, Andrew B. Kahng, Puneet Sharma, University of California at San Diego

6:35pm

4B.4

Analysis and Design of LVTSCR-Based EOS/ESD Protection Circuits for Burn-In Environment

O. Semenov, H. Sarbishaei, M. Sachdev, University of Waterloo

Session 4C
San Martin Room
5:15PM – 6:50PM

Analog Test and BIST

Chairs: Spyros Tragoudas, Southern Illinois University Carbondale
Li-C Wang, University of California at Santa Barbara

5:15pm

Introduction

5:20pm

4C.1

Built-In-Self-Testing Techniques for Programmable Capacitor Arrays

Amit Laknaur, Haibo Wang, Southern Illinois University Carbondale

5:50pm

4C.2

A Co-design Tool to Validate And Improve an FPGA Based Test Strategy for High Resolution Audio ADC

Daniela De Venuto, Grazia Marchione, Leonardo Reyneri, Politecnico di Bari, Italy

6:20pm

4C.3

A Built-In Self-Test Scheme for Differential Ring Oscillators

Dermentzoglou Lampros, Tsiatouhas Yiorgos, Arapoyanni Angela, National and Kapodistrian University of Athens

6:35pm

4C.4

Power Reduction in Test-Per-Scan BIST with Supply Gating and Efficient Scan Partitioning

Swarup Bhunia, Hamid Mahmoodi, Kaushik Roy, Purdue University

Session EP2 Panel Discussion & Dinner

Donner Pass Room

7:00PM -9:00PM

Nanoelectronics: Evolution or Revolution?

Panel Organizer: Ali Keshavarzi, Intel

Panel Moderator: (tbd)

Scaling of CMOS technology continues in spite of tremendous technology development barriers, design challenges and prohibitive costs. Today, the 65nm CMOS technology node is moving from development to high volume manufacturing while research and development continues on future technology nodes including 45nm, 30nm and beyond. Design of ICs in these scaled technologies faces new limitations. It is increasingly difficult to sustain supply and threshold voltage scaling to provide the required performance increase, limit energy consumption, control power dissipation, and maintain reliability. These requirements pose several difficulties across a range of disciplines spanning technology, fabrication, transistor structure, circuits, systems, design, and architecture.

On the technology front, the question arises whether we can continue to scale CMOS technology and whether we are close to the end of the ITRS roadmap. Are there any fundamental barriers? Should we continue along the traditional CMOS scaling path - reduce effective oxide thickness, improve channel mobility, and minimize parasitic - or consider a more radical departure from planar CMOS to non-planar device structures such as tri-gate and FinFET thin body transistors? Will we ever use nanowires and other novel nano devices such as Carbon nanotubes and self-assembled molecular devices? How important is self-assembly and bottom-up manufacturing in making future systems? What options do we have post non-planar CMOS and before more exotic spintronics and quantum devices? On the design front, while researchers are addressing various circuit design techniques to deal with process variation and leakage, it is unclear whether we can build systems with non-planar CMOS devices and other novel nano devices. Do we need new circuit design methods? How do we put systems together either with aggressively scaled Si devices, non-planar CMOS or with self-assembled molecular devices? What are the implications for design community? Will the information processing paradigm shift? Will we learn anything from researching futuristic nanoscale devices, circuits and systems that may impact scaling of Silicon CMOS technology?

Panelists:

Mark Lundstrom, Purdue University

Philip Wong, Stanford University and formerly IBM

Kazuo Yano, Hitachi - Research

Plenary Session 2P**Donner Pass Room****8:30AM - 10:15AM**

Co-Chairs: **Kris Verma**
Silicon Valley Technical Institute
Lech Jozwiak
Eindhoven University of Technology, The Netherlands

8:30am**Introduction & Announcements****8:45am****2P.1****Quality and EDA**

Aki Fujimura
Chief Technology Officer
Cadence Design Systems

Quality has many definitions. Conformance to specifications; Customer Satisfaction; Delivery divided by Expectations; etc. EDA's sense of quality is determined by what it's customers want. Do we have a virtuous cycle in the quality relationship between EDA and its customers? EDA is also the quality tools supplier to help the Electronics Systems and semiconductor companies to produce quality products on time. The speaker will examine both aspects of the quality issue from an EDA perspective.

9:15am**2P.2****IP Quality: A New Model that Faces Methodology and Management Challenges**

Kurt A. Wolf
Director, Library Management Division
TSMC

The promised value and productivity from re-aggregating the IC design chain isn't always delivered, in part because of isolated IP product development/quality related practices, and in part because of an inability, from a design management perspective, to see "big picture" issues in the IP marketplace. However, these challenges are not insurmountable.

The concern over IP quality has rightfully grown over the past years as the future growth of the IC industry depends on two factors; a) achieving higher levels of design productivity and b) shifting internal resources towards creating and delivering value-added user benefits that stimulate increased end-product consumption. While the second factor is not discussed in this presentation, there's a presumption that higher IP quality and productivity enables a shift of resources to more applications-oriented design.

A pre-requisite to achieving the productivity gains is substantial improvements in the level of IP quality, coupled with increased forethought during product development. This presentation describes a methodology to evaluate IP for SOC integration. The focus is on development & quality verification practices that also account for the issues of IP integration.

Additionally, the long-term growth of the semiconductor industry may be limited by the lack of value placed on collaboration, support, quality verification, and due diligence between SOC design teams and their IP partners.

This presentation also describes improvements in the Hard IP business relationship between these groups that enable dramatic growth through slight changes in communications models.

By developing reasonable expectations and focusing on open discussion between each group, perspective begins to shift. The true value of the design team and IP partnership is a function of successful collaborations – not when the user squeezes the last drop out of NRE, royalty, per-use, or other financing models. And the value-add of the partnership is realized when that collaboration includes additional real, shared incentives that more fully value the IP industry, rather than focus on purely lowest cost.

9:45am**2P.3****SoC Engineering Trends as Impacted by New Applications and System Level Requirements**

Bernard Candaele
Department Head, SoC, IC & EDA

Thales, Paris Colombes, France

The SoC increasing integration scale as well as the system and customer requirements are important factors for a complete revisit of the development models for electronic products. New customer models ask for software driven electronics. Software engineering is moving to a component-based and MDA development approach to be applied to embedded applications. Hardware engineering is moving to SSDI System Level Development and Reuse methodologies. The 2 approaches have now to be further developed and combined for next generations SoC's to get high quality and adaptable designs at a reasonable development cost. New application-level quality standards have also to be part of the complete development flow.

It is demonstrated through several examples these new methodologies: system engineering methodology on software radios (UML, PIM Platform Independent Model and PSM Platform Specific Model) and its current extension to the hardware parts (SCA, OCP potential extensions), system engineering in line with the Common Criteria development and qualification process for new security products (PP Protection Profile and ST Security Target,...), development and validation methodology in line with DO254 standard for new safety products in avionics (formal verifications, ...). Impacts on SoC architectures and design techniques will be discussed during the talk.

Session 5A

San Carlos Room

10:30AM - 12:00PM

Design Methods and Tools in DSM

Chairs: Vamsi Srikantam, Agilent Laboratories
James Lei, Altera

10:30am

Introduction

10:35am

5A.1

ASLIC: A Low Power CMOS Analog Circuit Design Automation

Jihyun Lee, Yong-Bin Kim

11:05am

5A.2

Modeling MOS Snapback for Circuit-Level ESD Simulation Using BSIM3 and VBIC Models

Yuanzhong (Paul) Zhou, Duane Connerney, Ronald Carroll, Timwah Luk, Fairchild Semiconductor

11:35am

5A.3

A Mask Reuse Methodology for Reducing System-on-a-Chip Cost

Subhrajit Bhattacharya, John A Darringer, Daniel L. Ostapko, Youngsoo Shin, IBM

Session 5B

San Juan Room

10:30AM - 12:00PM

Design Techniques for Leakage Reduction

Chairs: David Overhauser, Cadence Design Systems
Adrian Ionescu, Swiss Federal Institute of Technology (EPFL)

10:30am

Introduction

10:35am

5B.1

Design of High Performance Sense Amplifier Using Independent Gate Control in sub-50nm Double-Gate MOSFET

Saibal Mukhopadhyay, Hamid Mahmoodi, Kaushik Roy, Purdue University

11:05am

5B.2

Simulating and Improving Microelectronic Device Reliability by Scaling Voltage and Temperature

Xiaojun Li, Joerg D. Walter, Joseph B. Bernstein, University of Maryland

11:35am

5B.3

Predicting and Designing for the Impact of Process Variations and Mismatch on the Trim Range and Yield of Bandgap References

Vishal Gupta, Gabriel A. Rincon-Mora, Georgia Institute of Technology

Session 5C

San Martin Room

10:30AM - 12:00PM

Variability Issues in Nanoscale Circuits

Chairs: *Sharad Saxena, PDF Solutions*

Nikos Konofaos, University of Patras, Greece

10:30am

Introduction

10:35am

5C.1

Modeling Intrinsic Fluctuations in Decanometer MOS Devices due to Gate Line Edge Roughness (LER)

Norman Gunther, Emad Hamadeh**, Darrell Niemann*, Iliya Pesic***, Mahmud Rahman*, * Santa Clara University, ** Applied Micro Circuits Corp., *** Silvaco*

11:05am

5C.2

Modeling Within-Die Spatial Correlation Effects for Process-Design Co-Optimization

Paul Friedberg, Yu Cao, Jason Cain, Ruth Wang, Jan Rabaey, Costas Spanos, University of California at Berkeley

11:35am

5C.3

Robust Multi-Level Current-Mode On-Chip Interconnect Signaling in the Presence of Process Variations

Vishak Venkatraman, Wayne Burleson, University of Massachusetts Amherst

Session 6A

San Carlos Room

1:00PM - 3:05PM

Issues in Noise and Timing

Chairs: *Rajeev Murgai, Fujitsu Laboratories of America*

Eileen You, Cadence Design Systems

1:00pm

Introduction

1:05pm

6A.1

A Comprehensive Methodology for Noise Characterization of ASIC Cell Libraries

Sreeram Chandrasekar, Gaurav Kumar Varshney, V. Visvanathan, Texas Instruments

1:35pm

6A.2

Sensitivity-Based Gate Delay Propagation in Static Timing Analysis

Shahin Nazarian*, Massoud Pedram*, Emre Tuncer**, Tao Lin**, *University of Southern California, **Magma Design Automation

2:05pm

6A.3

Fast Decap Allocation Algorithm for Robust On-Chip Power Delivery

Zhenyu Qi*, Hang Li*, Sheldon X.-D. Tan*, Lifeng Wu**, Xianlong Hong***, *University of California Riverside, **Cadence, Yici Cai***, ***Tsinghua University, China

2:35pm

6A.4

Clock trees: differential or single ended?

Deepak Sekar, Georgia Institute of Technology

Session 6B
San Juan Room
1:00PM - 3:05PM

Design Approaches for System in Package (SiP)

Chairs: **Lalitha Immaneni**, Intel
Ravi Mahajan, Intel

1:00pm

Introduction

1:05pm

6B.1

Exploring the challenges in creating a high-quality mainstream design solution for System-in-Package (SiP) design

Bill McCaffrey, Cadence Design Systems

1:35pm

6B.2

Design and Analysis of Area-IO DRAM/Logic integration with System-in-a-Package

Anru Wang, Wayne Dai, University of California at Santa Cruz

2:05pm

6B.3

Physical Design of Optoelectronic System-On-A-Package: A Cad Tool and Algorithms

Chung-Seok(Andy) Seo, Abhijit Chatterjee, Nan M. Jokerst

2:35pm

6B.4

Concurrent Chip Package Design for Global Clock Distribution Using Standing Wave Approach

Meigen Shen, Li-Rong Zheng, Hannu Tenhunen

Session 6C
San Martin Room
1:00PM - 3:05PM

DSM Interconnect Issues

Chairs: **Farzan Fallah**, Fujitsu Laboratories of America
Norman Chang, Apache Design Solutions

1:00pm

Introduction

1:05pm

6C.1

Current Calculation on Signal Interconnects

Muzhou Shao, Youxin Gao, Lipen Yuan, Martin Df Wong, Hungming Chen, Synopsys Inc.

1:35pm

6C.2

Dummy Filling Methods for Reducing Interconnect Capacitance and Number of Fills

Atsushi Kurokawa, Toshiki Kanamoto, Tetsuya Ibe, Akira Kasebe, Chang Wei Fong, Tetsuro Kage, Yasuaki Inoue, Hiroo Masuda, STARC Japan

2:05pm

6C.3

Voltage Scaling, Wire Sizing and Repeater Insertion Design Rules for Wave-Pipelined VLSI Global Interconnect Circuits

Vinita V. Deodhar, Jeffrey A. Davis, Georgia Institute of Technology

2:35pm

6C.4

Interconnect Delay and Slew Metrics Using the First Three Moments

Jiaxing Sun, Yun Zheng, Qing Ye, Tianchun Ye

2:50pm

6C.5

Passive Hierarchical Model Order Reduction and Realization of RLCM Circuits

Pu Liu, Zhenyu Qi, Sheldon X.-D. Tan, University of California Riverside

Session 7A
San Carlos Room
3:30PM – 5:35PM

Advances in Floor Planning

Chairs: Marco Casale-Rossi, STMicroelectronics

Tanay Karnik, Intel

3:30pm

Introduction

3:35pm

7A.1

Reticle Floorplanning and Wafer Dicing for Multiple Project Wafers

Meng-Chiou Wu, Rung-Bin Lin, Yuan Ze University, Taiwan

4:05pm

7A.2

Obstacle-Avoiding Rectilinear Minimum-Delay Steiner Tree Construction towards IP-Block-Based SOC Design

Jingyu Xu, Xianlong Hong, Tong Jing, Yang Yang, Tsinghua University, China

4:35pm

7A.3

Wire Planning with Bounded Over-the-Block Wires

Hua Xiang, I-Min Liu, Martin D.F. Wong, IBM

5:05pm

7A.4

Floorplanning with Consideration of White Space Resource Distribution for Repeater Planning

Song Chen, Xianlong Hong, Sheqin Dong, Yuchun Ma, Chung-Kuan Cheng, Tsinghua University, China

5:20pm

7A.5

Thermal-Aware Floorplanning Using Genetic Algorithms

W. Hung, Y. Xie, N. Vijaykrishnan, C. Addo-Quaye, T. Theocharides, M. J. Irwin, Penn State University

Session 7B

San Juan Room

3:30PM – 5:35PM

Issues in On-Chip Communication and Analog/RF Designs

Chairs: *Amit Mehrotra, Berkeley Design Automation*
George Alexiou, University of Patras and Computer Technology Institute, Greece

3:30pm

Introduction

3:35pm

7B.1

Joint Equalization and Coding for On-Chip Bus Communication

Srinivasa R. Sridhara, Ganesh Balamurugan**, Naresh R. Shanbhag*, *University of Illinois at Urbana-Champaign, **Intel*

4:05pm

7B.2

A More Effective C_{eff}

Sani R. Nassif, Zhuo Li**, *IBM, **Texas A&M University*

4:35pm

7B.3

An Interconnect Insensitive Linear Time-Varying Driver Model for Static Timing Analysis

Chung-Kuan Tsai, Malgorzata Marek-Sadowska, University of California at Santa Barbara

5:05pm

7B.4

Design a Band-pass Pseudo-2-path Switched Capacitor Ladder Filter

A. Zahabi, O. Shoaie, Y. Koolivand, University of Tehran, IRAN

5:20pm

7B.5

Design Considerations for Low-Power Ultra Wideband Radio Receivers

Payam Heydari, University of California, Irvine

Session 7C
San Martin Room
3:30PM – 5:35PM

Robust Design under Parameter Variations

Chairs: Ravi Joshi, IBM
Sarma Vrudhula, Arizona State University

3:30pm

Introduction

3:35pm

7C.1

A New Method for Robust Design of Digital Circuits

Dinesh Patil, Sunghee Yun, Seung-Jean Kim, Alvin Cheung, Mark Horowitz, Stephen Boyd, Stanford University

4:05pm

7C.2

Analysis and Synthesis of Staggered Twisted Bundle for Crosstalk Reduction

Hao Yu, Lei He, University of California at Los Angeles

4:35pm

7C.3

Analysis of Wave-Pipelined Domino Logic Circuit and Clocking Styles Subject to Parametric Variations

Wei Ling, Yvon Savaria, l'École Polytechnique de Montréal

5:05pm

7C.4

Impact of Interconnect Process Variations on Memory Performance and Design

Andres Teene, Bob Davis, Ruggero Castagnetti, Jeff Brown, Shiva Ramesh, LSI Logic